

### **CLAIMS**

The current claim set of the application is presented below. Indications as to the status of the claims (“original”, “currently amended”, “cancelled”, “new”, etc.) appear in parentheses after the claim number. Deletions are identified in bold with single brackets and strikethrough (e.g. [~~deletion~~]) and new text is identified with underlining (e.g. new language).

#### **Listing of Claims:**

1-22. Cancelled

23. (Previously presented) A method of forming a relief pattern in a photoresist substrate, the method comprising:

a) providing a photosensitive laminate structure comprising at least an ink receptive, radiation transmissive layer comprising polyvinyl alcohol and inorganic particles, and at least one photosensitive resist layer formed into a single, photosensitive laminate;

b) printing a pattern on the ink receptive, radiation transmissive layer;

c) exposing the laminate to actinic radiation to modify the photosensitive resist layer; and

d) removing a portion of the photosensitive resist layer corresponding to the pattern formed on the ink receptive, radiation transmissive layer.

24. (Original) The method according to claim 23, further comprising removing the ink receptive, radiation transmissive layer.

25. (Original) The method according to claim 24, wherein the ink receptive, radiation transmissive layer is removed following application of water.